

AMENDMENTS TO THE CLAIMS

1. (Original) A charged particle detection system, comprising:
 - (a) an electronic multiplexing unit in proximity to
 - (b) a plurality of charge-collecting zones,wherein each charge-collecting zone comprises a conductive material for receiving and storing charge,
wherein each charge-collecting zone is isolated and electrostatically shielded from neighboring charge-collecting zones by a separator comprising an insulated electrical conductor held at a reference potential,
wherein each charge-collecting zone is electronically interfaced to the multiplexing unit, and
wherein the multiplexing unit is interfaced to a means for measuring the charge collected by the charge-collecting zones.
2. (Original) The system of Claim 1, wherein the multiplexing unit effects switching through sequencing using a Gray-code.
3. (Original) The system of Claim 1 having a duty cycle for charge collecting in charge-collecting zones greater than 98% for each readout cycle.
4. (Original) The system of Claim 1, wherein the separator is comprised of insulating and conducting layers.
5. (Original) The system of Claim 4, wherein the insulating layer comprises a high dielectric strength, low-leakage material.
6. (Original) The system of Claim 4, wherein the conducting layer comprises aluminum.

LAW OFFICES OF
CHRISTENSEN O'CONNOR JOHNSON KINDNESS^{PLLC}
1420 Fifth Avenue
Suite 2800
Seattle, Washington 98101
206.682.8100

7. (Original) The system of Claim 4, wherein the insulating layer comprises aluminum oxide.
8. (Original) The system of Claim 1, wherein the separator supports the charge collecting zones.
9. (Original) The system of Claim 1, wherein the conductive material comprises a metal selected from the group consisting of copper, chromium, gold, and mixtures thereof.
10. (Original) The system of Claim 1, wherein the conductive material comprises vapor deposited chromium and gold.
11. (Original) The system of Claim 1, wherein at least one charge-collecting zone comprises a Faraday cup.
12. (Original) The system of Claim 11, wherein each Faraday cup has an aspect ratio greater than about 2:1.
13. (Original) The system of Claim 1, wherein the plurality of charge-collecting zones is a Faraday cup detector array.
14. (Original) The system of Claim 1, wherein the plurality of charge-collecting zones is a linear array of Faraday cups.
15. (Original) The system of Claim 1, wherein the plurality of charge-collecting zones is a two-dimensional array of Faraday cups.
16. (Original) The system of Claim 1, wherein the plurality of charge-collecting zones comprises a stack of Faraday cups.
17. (Original) The system of Claim 1, wherein the system measures absolute ion current.
18. (Original) The system of Claim 1, wherein the system measures ion currents from about 0.2 pA to about 1.4 μ A.

19. (Original) The system of Claim 1, wherein the plurality of charge-collecting zones comprises 2^n zones, wherein n is an integer greater than zero.

20. (Original) The system of Claim 1, wherein the plurality of charge-collecting zones comprises 256 zones.

21. (Original) The system of Claim 1, wherein the a means for measuring the charge collected by charge-collecting zones is selected from an operational-amplifier and an operational-amplifier-integrator.

22. (Original) The system of Claim 1, further comprising a mask having a first surface facing the charge-collecting zones and a second surface facing outward from the charge-collecting zones, wherein the first surface is nonconductively attached to the charge-collecting zones, and wherein the second surface comprises an electrically conductive surface.

23. (Original) The system of Claim 22, wherein the mask carries a suppressor grid held at a predetermined potential.

24. (Original) The system of Claim 1, further comprising a heating means for increasing the temperature of the charge-collecting zones.

25. (Original) The system of Claim 1, further comprising a temperature control means for controlling the temperature of the system.

26. (Original) The system of Claim 1, wherein the separator, the plurality of charge-collecting zones, the electronic multiplexing unit, and the means for measuring the charge collected by charge-collecting zones are mounted on a single substrate.

27. (Original) The system of Claim 26, wherein the substrate comprises a printed circuit board having traces.

28. (Original) The system of Claim 27, wherein the traces are electrically connected to the charge-collecting zones directly.

29. (Original) The system of Claim 1, wherein the plurality of charge-collecting zones is microfabricated.

30. (Original) The system of Claim 29, wherein the plurality of charge-collecting zones comprises a Faraday cup detector array.

31. (Original) The system of Claim 29, wherein the plurality of charge-collecting zones comprises an array of Faraday cups, each cup having a unit cell size of about 100 μm .

32. (Original) The system of Claim 29 microfabricated by a deep reactive ion etching process.

33. (Original) The system of Claim 29 microfabricated by a lithographie-galvanoformung-abformung process.

34. (Original) A method for measuring charged particle beam intensity, comprising impinging a charged particle beam onto a charged particle beam detector system, wherein the charged particle beam detection system comprises;

(a) an electronic multiplexing unit in proximity to

(b) a plurality of charge-collecting zones,

wherein each charge-collecting zone comprises a conductive material for receiving and storing charge,

wherein each charge-collecting zone is isolated and electrostatically shielded from neighboring charge-collecting zones by a separator comprising an insulated electrical conductor held at a reference potential,

wherein each charge-collecting zone is electronically interfaced to the multiplexing unit, and

wherein the multiplexing unit is interfaced to a means for measuring the charge collected by the charge-collecting zones.

35. (Original) The method of Claim 34, wherein the detection system further comprises a mask having a first surface facing the charge-collecting zones and a second surface facing outward from the charge-collecting zones, wherein the first surface is nonconductively attached to the charge-collecting zones, and wherein the second surface comprises an electrically conductive surface.

36. (Original) The system of Claim 35, wherein the mask carries a suppressor grid held at a predetermined potential.

37. (Original) The method of Claim 36, wherein the predetermined potential reduces loss of charged particles originating from sputtering after collection of a highly energetic charged particle.

38. (Original) The method of Claim 34, wherein at least one charge-collecting zone comprises a Faraday cup.

39. (Original) The method of Claim 34, wherein the plurality of charge-collecting zones comprises a Faraday cup detector array.

40. (Original) A charged particle analyzer or charged particle separator, comprising:

- (a) a source of charged particles;
- (b) means for forming a beam of charged particles; and
- (c) means for directing the beam onto a charged particle beam detection system, wherein the charged particle beam detection system comprises:
 - (i) an electronic multiplexing unit in proximity to
 - (ii) a plurality of charge-collecting zones,wherein each charge-collecting zone comprises a conductive material for receiving and storing charge,

wherein each charge-collecting zone is isolated and electrostatically shielded from neighboring charge-collecting zones by a separator comprising an insulated electrical conductor held at a reference potential,

wherein each charge-collecting zone is electronically interfaced to the multiplexing unit, and

wherein the multiplexing unit is interfaced to a means for measuring the charge collected by the charge-collecting zones.

41. (Original) The analyzer of Claim 40, wherein the detection system further comprises a mask having a first surface facing the charge-collecting zones and a second surface facing outward from the charge-collecting zones, wherein the first surface is nonconductively attached to the charge-collecting zones, and wherein the second surface comprises an electrically conductive surface.

42. (Original) The analyzer of Claim 41, wherein the mask carries a suppressor grid held at a predetermined potential.

43. (Original) The analyzer of Claim 40, wherein each charge-collecting zone comprises a Faraday cup.

44. (Original) The analyzer of Claim 40, wherein the plurality of charge-collecting zones comprises a Faraday cup detector array.

45. (Currently amended) A charged particle analyzer comprising the ion beam detection system according to ~~any one of Claims 1 to 39~~ Claim 1.

46. (Original) The charged particle detection system of Claim 13 wherein the FCDA is constructed from a compressed sandwich of precision-cut laminates and shims defining the Faraday cups and electrostatic separators.

47. (Original) The charged particle detection system of Claim 13 wherein the FCDA is constructed from a block of oxidizable metal bonded onto an insulating substrate with a metal oxide forming the insulation layer and high aspect ratio machined channels forming the Faraday cups.

48. (Original) The charged particle detection system of Claim 47 wherein the FCDA is constructed from a hard anodized metal selected from the group consisting of aluminum, copper, nickel, and titanium.

49. (Original) The charged particle detection system of Claim 47 wherein the FCDA is constructed using electric discharge machining (EDM) of a hard anodized metal selected from the group consisting of aluminum, copper, nickel, and titanium.

50. (Original) The charged particle detection system of Claim 13 wherein the FCDA is constructed as an additive deposition or template electroplating of high aspect ratio metal regions to form the Faraday cups and their electrostatic separators.

51. (Original) The charged particle detection system of Claim 50 wherein the high aspect ratio metal parts are created by Lithography-Galvanoformung-Abformung (LIGA).

52. (Original) The charged particle detection system of Claim 50 wherein the high aspect ratio metal parts are created by deep ultraviolet photolithography of thick photoresist.

53. (Original) The charged particle detection system of Claim 13 wherein the FCDA is constructed by subtractive etching of a single crystal semiconductor wafer or chip with a high aspect ratio to form the Faraday cups.

54. (Original) The charged particle detection system of Claim 53 wherein silicon comprises the conducting layer.

55. (Original) The charged particle detection system of Claim 53 wherein silicon dioxide comprises the insulating layer.

56. (Original) The charged particle detection system of Claim 53 wherein gallium arsenide comprises the conducting layer.

57. (Original) The charged particle detection system of Claim 53 wherein deep reactive ion etching (DRIE) is used to etch the Faraday cups.

58. (Original) The charged particle detection system of Claim 53 wherein the FCDA is formed on the same wafer or chip as other active electronic circuitry.

59-88. (Canceled)

LAW OFFICES OF
CHRISTENSEN O'CONNOR JOHNSON KINDNESS^{PLLC}
1420 Fifth Avenue
Suite 2800
Seattle, Washington 98101
206.682.8100